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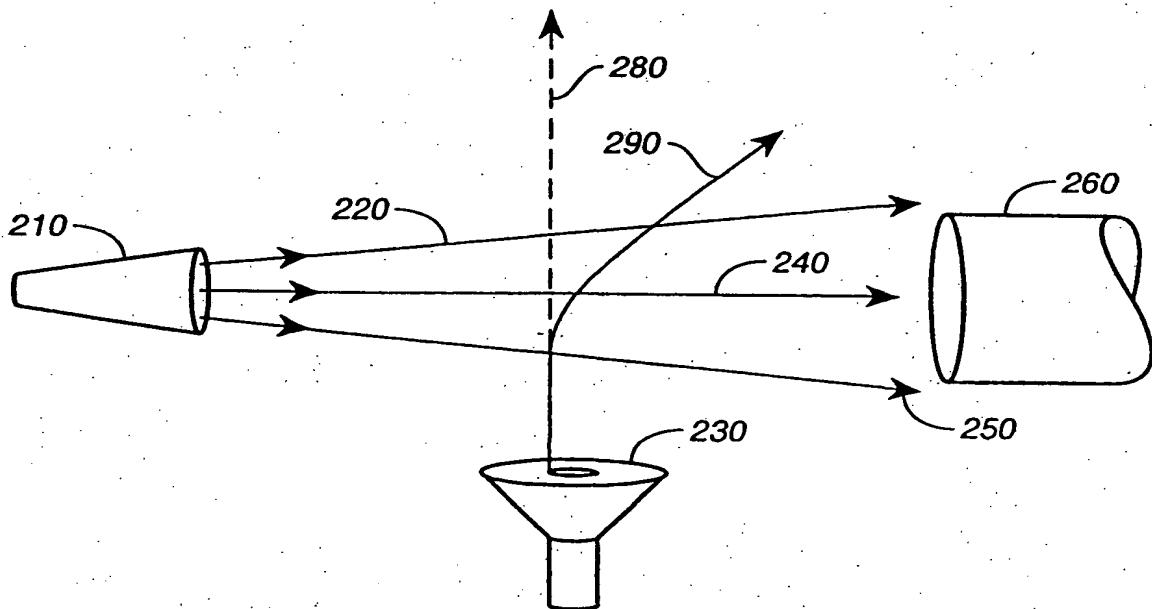
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(54) Title: DISCHARGE SOURCE WITH GAS CURTAIN FOR PROTECTING OPTICS FROM PARTICLES



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(57) Abstract: A gas curtain device is employed to deflect debris that is generated by an extreme ultraviolet and soft x-ray radiation discharge source such as an electric discharge plasma source. The gas curtain device projects a stream of gas over the path of the radiation to deflect debris particles into a direction that is different from that of the path of the radiation. The gas curtain can be employed to prevent debris accumulation on the optics used in photolithography.